

## CURRICULUM VITAE

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7. Professional experiences
  - Lecturer, Department of Chemical Engineering ITS, 1990-2009
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8. Professional Memberships:
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  - American Chemical Society
  - Indonesian Nanotechnology Society
  - Material Research Society – Indonesia
9. Publications
  1. A. Nur, H. Setyawan, An experimental and theoretical investigation of the formation of hydroxyapatite particles prepared by an electrochemical method, *Journal of Chemical Engineering of Japan* (IF 0.61), 49(2), 144-151 (2016).
  2. H. Setyawan, M. Yuwana, R. Balgis, PEG-templated mesoporous silicas using silicate precursor and their applications in desiccant dehumidification cooling systems, *Microporous and Mesoporous Materials* (IF 3.453), 218, 95-100 (2015).
  3. N.A. Rahman, I. Widhiana, S.R. Juliastuti, H. Setyawan, Synthesis of mesoporous silica with controlled pore structure from bagasse ash as a silica source, *Colloids and Surfaces A: Physicochemical and Engineering Aspects* (IF 2.354), 476, 1-7 (2015).
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  5. S. Muljani, H. Setyawan, G. Wibawa, A. Altway, A facile method for the production of high-surface area mesoporous silica gels from geothermal sludge, *Adv. Powder Technol.*, 25, 1593–1599 (2014).
  6. N. Nazriati, H. Setyawan, S. Affandi, M. Yuwana, S. Winardi, Using bagasse ash as a silica source when preparing silica aerogels via ambient pressure drying, *J. Non-Cryst. Solid*, 400, 6-11 (2014).
  7. H. Setyawan, F. Fajaroh, M.D. Pusfitasari, M. Yuwana, S. Affandi, A facile method to prepare high-purity magnetite nanoparticles by electro-oxidation of iron in water using a pulsed direct current, *Asia-Pac. J. Chem. Eng.*, 9, 768-774 (2014).
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  9. A. Nur, H. Setyawan, A. Widjaja, I.W. Lenggoro, Electrochemical processes for the formation of

- hydroxyapatite powders, *Bull. Chem. React. Eng. Catal.*, **9**, 168-175 (2014).
10. T. Ogi, N. Tajima, R. Balgis, H. Setyawan, K. Okuyama, Influence of formic acid on the electrochemical properties of high porosity Pt/TiN nanoparticles aggregate synthesised via self-assembly assisted spray pyrolysis, *AIChE J.*, **59**, 2753–2760 (2013).
  11. F. Fajaroh, H. Setyawan, A. Nur, I.W. Lenggoro, Thermal stability of silica-coated magnetite nanoparticles prepared by an electrochemical method, *Adv. Powder Technol.*, **24**, 507–511 (2013).
  12. H. Setyawan, F. Fajaroh, W. Widiyastuti, S. Winardi, I.W. Lenggoro, N. Mufti, One-step synthesis of silica-coated magnetite nanoparticles by electrooxidation of iron in sodium silicate solution, *J. nanopart. Res.*, **14**, 807:1-9 (2012).
  13. F. Fajaroh, H. Setyawan, W. Widiyastuti, S. Winardi, Synthesis of magnetite nanoparticles by surfactant-free electrochemical method in an aqueous system, *Adv. Powder Technol.*, **23**, 328-333 (2012).
  14. H. Setyawan, R. Balgis, Mesoporous silicas prepared from sodium silicate using gelatin templating, *Asia-Pac. J. Chem. Eng.*, **7**, 448-454 (2012).
  15. Affandi, S., Setyawan, H., Winardi, S., Purwanto, A. and Balgis, R., A facile method for production of high-purity silica xerogels from bagasse ash, *Advanced Powder Technology*, **20**, 468–472 (2009).
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